

**EAST Search History****EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S36	28193	((438/597,598,618,620,622-624,637) or (257/E21.575-E21.577,E21.579,E21.58-E21.585)).OCLS.	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2009/11/20 16:24
S37	17749	S36 and @ad<"20030529"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/11/20 16:24
S38	37	S37 and (((etch stop) or (hard mask)) with (SiCN\$3 or (silicon carbonitride)))	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/11/20 16:24
S39	490	(((etch stop) or (hard mask)) with (SiCN\$3 or (silicon carbonitride)))	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/11/20 16:24
S40	49	S39 and @ad<"20030529"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/11/20 16:24
S42	19529	(257/751,758,774,E21.577,E21.579,E21.584-E21.585).OCLS.	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2009/11/20 17:13

**EAST Search History (Interference)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S43	1	((third insulation film) and trench and via and (porous insulation film) and (insulation barrier layer) and (organic substance)).clm.	US-PGPUB; USPAT; UPAD	ADJ	ON	2009/11/20 16:35

**11/20/2009 6:45:57 PM**

**C:\Documents and Settings\bau\My Documents\EAST\Workspaces\Metallization\Sealing of Openings  
 \10558367 insulation barrier layer in trench and via of porous ILD.wsp**